	Type	L #	Hits	DBs	Search Text	Time Stamp
1	BRS	L1	115	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction)	2007/07/17 08:26
2	BRS	L2	0	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask same recticle)	2007/07/17 08:27
3	BRS	L3	0	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and recticle)	2007/07/17 08:27
4	BRS	L4	76	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle)	2007/07/17 08:27
5	BRS	L5	3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect)	2007/07/17 08:28

	Type	L #	Hits	DBs	Search Text	Time Stamp
6	BRS	L6	27	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect)	2007/07/17 08:28
7	BRS	L7	23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer	2007/07/17 08:29
8	BRS	L8	23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions	2007/07/17 08:29
9	BRS	L9	23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions and (lithog$7)	2007/07/17 08:30
10	BRS	L10	23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions and (lithog$7) and compen$6	2007/07/17 08:32

	Type	L #	Hits	DBs	Search Text	Time Stamp
11	BRS	L11	7	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions and (lithog$7) and compen$6 and table	2007/07/17 08:37
12	BRS	L12	5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions and (lithog$7) and compen$6 and table and bias	2007/07/17 08:46
13	BRS	L13	5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	(optical adj process adj correction) and (mask and reticle) and (etch same effect) and wafer and distortions and (lithog$7) and compen$6 and table and bias and (simulation simulate)	2007/07/17 08:48
14	BRS	L14	73	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	703/13.ccls. and @pd>="20070215"	2007/07/17 08:54
15	BRS	L15	83	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	716/21.ccls. and @pd>="20070215"	2007/07/17 08:54